For Finishing Si Wafers / Nanomate Premium

Outstanding Performance in Final Mirror-Finishing of Silicon Wafers and Device BG

Ultra fine diamond grit and Ultra fine ceramics revolutionized the conventional wisdom of grinding wheels. Application of both acquired material technology and production technology has allowed Ultra fine grinding. Its effectiveness to reduce grinding damage in layers of brittle material such as polish-reduction of ϕ 300 mm silicon wafer and prevent cracks on a thin layer device wafer.



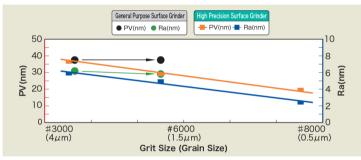
Features

- ·Extremely flat, low damage, and smooth grinding possible.
- •Grinding of 300 mm silicon wafers as thin as 3 μ m is possible.
- ·Polished surface quality equivalent to polishing is possible.

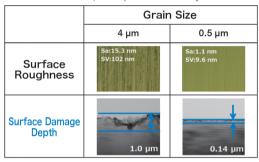
Applications

·Ultra-precision surface grinding of various semiconductor wafers

Relation Between Grit Size and Surface Wafer



12 Inch Si Wafer / Comparison Data by Grain Size



For Si Wafers / Nanomate Cellfied

Demonstrates Performance in Si as Sliced Wafer Grinding

It has a bond structure with high porosity and excellent chip evacuation, and achieves both lower load and longer life in the processing of silicon wafers.



·Achieves both low load processing and long life

Applications

·Thickness processing of as-sliced Si wafers

Machining Examples

□Comparison with Conventional Wheel (Nanomate V-Heart)

1) Machine Vertical Axis Rotary Surface Grinder

2) Wheel Specification ①Conventional Wheel ②Nanomate Cellfied

Ф200-3W #4000(3 um)

3)Workpiece 12 inch Silicon Wafer

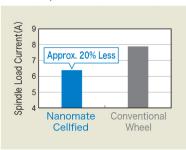
4) Coolant City Water

5) Conditions Wheel Rotation Speed: 1,500 min-1

Chuck Rotation Speed:300 min-1

Spark Out: 5 sec

Spindle Load Current



Wheel Wear Rate

